Special Issue

Plasma Technology and Application

Message from the Guest Editor

Plasma today plays a key role in physical and technological research environments, as much as in industrial chemistry, space research and fusion.New applications of plasmas continue to accelerate at an increasing rate, e.g., in the treatment of materials, or developments in medical and healthcare machinery. Among the scenarios opened up by the generation of plasmas, a key challenge is to accelerate high-quality particles for the controlled production of secondary radiation, such as x-rays. In this and the other above-mentioned cases, the study and technological development of the plasma source, including the diagnostics required to detect its characteristics, is therefore essential. This Special Issue will be devoted to advances in plasma source technology studied and used in nuclear physics or accelerator physics research environments.

Guest Editor

Dr. Gemma Costa
Laboratori Nazionali di Frascati (LNF), Istituto Nazionale di Fisica Nucleare (INFN), 00044 Rome, Italy

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Applied Sciences
Editorial Office
MDPI, Grosspeteranlage 5
4052 Basel, Switzerland
Tel: +41 61 683 77 34
applsci@mdpi.com

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As the world of science becomes ever more specialized, researchers may lose themselves in the deep forest of the ever increasing number of subfields being created. This open access journal Applied Sciences has been started to link these subfields, so researchers can cut through the forest and see the surrounding, or quite distant fields and subfields to help develop his/her own research even further with the aid of this multi-dimensional network.

Editor-in-Chief

Prof. Dr. Giulio Nicola Cerullo
Dipartimento di Fisica, Politecnico di Milano, Piazza L. da Vinci 32,
20133 Milano, Italy

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